

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: N. William Parker et al.

Docket No.: 58884-0305279  
(MBS-0005US)

Serial No.: Continuation of 10/243,585

Group Art Unit:

Filing Date: July 28, 2003

Examiner:

For: **ELECTRON OPTICS FOR MULTI-BEAM ELECTRON BEAM  
LITHOGRAPHY TOOL**

**PRELIMINARY AMENDMENT**

Commissioner for Patents  
P. O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

Please enter this amendment prior to examination of the enclosed continuation application:

**AMENDMENT**

**IN THE CLAIMS**

Cancel claims 1-6 as filed in the parent application.

Add the following new claims:

1 7. (New) An electron optical column comprising:  
2 means for generating an electron beam;  
3 a focus lens; and  
4 an electrostatic scanning deflector situated above said focus lens, said scanning deflector  
5 comprising a first deflector and a second deflector configured to provide telecentric scanning of  
6 said electron beam on a specimen substrate positioned below said focus lens.

1 8. (New) An electron optical column as in claim 1, wherein said first deflector and said  
2 second deflector generate electric fields of opposite polarities.

1 9. (New) An electron optical column as in claim 1, wherein said first deflector and said